	Application No.	Applicant(s)		
	09/941,820	FLEMING ET AL.		
Notice of Allowability	Examiner	Art Unit		
	Savitri Mulpuri	2812		
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this a or other appropriate communication is subject	pplication. If not include on will be mailed in due	ed course. <b>THIS</b>	
<ol> <li>This communication is responsive to exam amdt prepared</li> <li>The allowed claim(s) is/are 61,63-70,73-76 and 80-83.</li> <li>The drawings filed on 28 August 2001 are accepted by the</li> <li>Acknowledgment is made of a claim for foreign priority una) All b) Some* c) None of the:         <ol> <li>Certified copies of the priority documents have</li> <li>Certified copies of the priority documents have</li> <li>Copies of the certified copies of the priority documents have</li> <li>Copies of the certified copies of the priority documents have</li> <li>Acknowledgment is made of a claim for domestic priority underence was included in the first sentence of the specification.</li> </ol> </li> <li>The translation of the foreign language provisional and acknowledgment is made of a claim for domestic priority underence of the specification.</li> </ol>	e Examiner.  Inder 35 U.S.C. § 119(a)-(d) or (f).  e been received.  e been received in Application No.  comments have been received in this  ation or in an Application Data Sheapplication has been received.  Inder 35 U.S.C. §§ 120 and/or 121	s national stage application since stage application since et. 37 CFR 1.78.	e a specific	
in the first sentence of the specification or in an Application Applicant has THREE MONTHS FROM THE "MAILING DATE" of below. Failure to timely comply will result in ABANDONMENT of	n Data Sheet. 37 CFR 1.78.  If this communication to file a reply	complying with the requ	irements noted	
7. A SUBSTITUTE OATH OR DECLARATION must be subminFORMAL PATENT APPLICATION (PTO-152) which give	nitted. Note the attached EXAMINE	R'S AMENDMENT or N		
<ul> <li>8.  CORRECTED DRAWINGS (as "replacement sheets") must (a)  including changes required by the Notice of Draftspers</li> <li>1)  hereto or 2)  to Paper No</li> <li>(b)  including changes required by the proposed drawing of (c)  including changes required by the attached Examiner'</li> </ul>	son's Patent Drawing Review(PTC	peen approved by the E		
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t			back) of	
9. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT FOR T			Note the	
Attachment(s)				
1 Notice of References Cited (PTO-892)	5☐ Notice of Informal F	Patent Application (PTO-	-152)	
2 Notice of Draftperson's Patent Drawing Review (PTO-948)	•	6⊠ Interview Summary (PTO-413), Paper No		
3 Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No	<sup>8</sup> ), 7⊠ Examiner's Amendr	ment/Comment		
4☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	8☐ Examiner's Stateme	Savitri Mulpuri Primary Examiner Art Unit: 2812	rance	

## **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr Hoheimer on 1/12/04. The application has been amended as follows:

Cancel claims 44-60

In claim 61, line 8 after "thereof," add ----and with the first and second materials being selected from the group consisting of polycrystalline silicon, amorphous silicon, silicon nitride, silicon dioxide, silicate glasses, III-V semiconductors, II-VI semiconductors, II-IV semiconductors, transparent oxides, sol-gel glasses, spin-on-glasses; -----

Cancel 62

In claim 70, line 5 after "form" add --- a four-layer periodic structure with a bandgap therein, and with each rod comprising a materials selected from the group consisting of polycrystalline silicon, amorphous silicon, silicon nitride, silicon dioxide, silicate glasses, III-V semiconductors, II-VI semiconductors, II-IV semiconductors, transparent oxides, sol-gel glasses, spin-on-glasses; ----

Cancel 71, 72

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In claim 76, line 8 after "hexagonal-pattern layer, " add ----and with the interconnected rods and the dots comprising the first material and with a second material filling in spaces between the interconnected rods of each-hexagonal-pattern layer and spaces between the dots of each interconnection layer, and with first and second materials being selected from the group consisting of polycrystalline silicon, amorphous silicon, silicon nitride, silicon dioxide, silicate glasses, III-V semiconductors, II-VI semiconductors, III-V semiconductors, transparent oxides, sol-gel glasses, spin-onglasses, gases and vacuum; ----

Cancel 78-79

Any inquiry concerning this communication should be directed to Savitri Mulpuri at telephone number 703.305.5184.

Savitri Mulpuri Primary Examiner Art Unit 2812